Claims

1. A method for exposing a light-sensitive layer (9) to light using an optical system (8) having an optical path, wherein at least one light beam (6, 6') is generated by at least one light source (7), respectively, and pixels (23) of an exposure pattern grid (24, 24', 24'', 24''') are illuminated by at least one micro-mirror device (1) with a plurality of micro-mirrors (3), characterised in that horizontal and/or vertical exposure pattern grid lines of the exposure pattern grid (24, 24', 24'', 24''') are sheared, wherein the shearing of a DMD-picture leaving the micro-mirror device (1) is effected along the optical path.

2. The method according to claim 1, wherein the horizontal and/or vertical exposure pattern grid lines are arranged so as to extend or be aligned in parallel to one another.

3. The method according to one of the preceding claims, wherein the horizontal and/or vertical exposure pattern grid lines are arranged obliquely.

4. A device for exposing a light-sensitive layer (9) to light using an optical system (8) having
   - at least one light source (7) for generating at least one light beam (6, 6'),
   - at least one micro-mirror device (1) with a plurality of micro-mirrors (3), wherein each micro-mirror (3) serves to illuminate one pixel (23) of an exposure pattern grid (24, 24', 24'', 24'''),

   characterised in that horizontal and/or vertical exposure pattern grid lines of the exposure pattern grid (24, 24', 24'', 24''') are sheared, wherein the shearing of a DMD-picture leaving the micro-mirror device (1) is effected along the optical path.